

WHAT IS CLAIMED IS:

1. An optical disk substrate, which has a central hole, comprising:

a first annular area for clamping, surrounding the outer edge of the central hole and including a first upper surface and a first lower surface thereon; and

a second annular area for forming an information storing area, surrounding the outer edge of the first annular area and including a second upper surface and a second lower surface thereon;

the first lower surface and the second lower surface being on the same plane, and the first upper surface being higher than the second upper surface.

2. The optical disk substrate as claimed in claim 1, wherein

the thickness of the first annular area is between 0.65 mm and 1.6 mm and its outer diameter is between 15.5 mm and 48 mm; and

the thickness of the second annular area is 0.6 mm and its outer diameter is 120 mm.

3. The optical disk substrate as claimed in claim 1, wherein the optical disk substrate is formed by applying injection molding method.

4. An optical disk, comprising:

an optical disk substrate with a central hole, which includes:

a first annular area for clamping, surrounding the outer edge of the central hole and including a first upper surface and a first lower surface thereon; and

a second annular area, surrounding the outer edge of the first annular area and including a second upper surface and a second lower surface thereon;

the first lower surface and the second lower surface being on the same plane, and the first upper surface being higher than the second upper surface; and

an information storing area, located on top of the second upper surface of the second annular area.

5. The optical disk as claimed in claim 4, wherein the information storing area includes:
at least one recording layer, located on top of the second upper surface of the second annular area;
a reflection layer, located on top of the at least one recording layer; and
a protection layer, located on top of the reflection layer.
6. The optical disk as claimed in claim 5, wherein the at least one recording layer is composed of dyestuff; and
the reflection layer is composed of metal.
7. The optical disk as claimed in claim 4, wherein the information storing area includes:
a first dielectric layer, located on top of the second upper surface of the second annular area;
a recording layer, located on top of the first dielectric layer;
a second dielectric layer, located on top of the recording layer;
a heat dissipating layer, located on top of the second dielectric layer;
a reflection layer, located on top of the heat dissipating layer; and
a protection layer, located on top of the reflection layer.
8. The optical disk as claimed in claim 7, wherein
the first dielectric layer and the second dielectric layer are composed of low dielectric constant material;
the recording layer is composed of alloy;
the heat dissipating layer is composed of metal; and
the reflection layer is composed of metal.
9. A method for fabricating an optical disk substrate, comprising the following steps:
fabricating a base plate having a third area and a fourth area, wherein the third area and the fourth area have the same thickness;

fabricating a compensation sheet, wherein the dimension of the compensation sheet is the same as that of the third area; and

assembling the compensation sheet and the base plate by joining the compensation sheet to the third area of the base plate.

10. The method for fabricating an optical disk substrate as claimed in claim 9, wherein the assembling step is achieved by bonding.

11. The method for fabricating an optical disk substrate as claimed in claim 9, wherein the assembling step is achieved by pressing.

12. A method for fabricating an optical disk, comprising the following steps:

fabricating an optical disk substrate with a central hole, wherein the optical disk substrate includes:

a first annular area for clamping, surrounding the outer edge of the central hole and including a first upper surface and a first lower surface thereon; and

a second annular area, surrounding the outer edge of the first annular area and including a second upper surface and a second lower surface thereon; the first lower surface and the second lower surface being on the same plane, and the first upper surface being higher than the second upper surface; and

forming an information storing area on top of the second upper surface of the second annular area.

13. The method for fabricating an optical disk as claimed in claim 12, wherein the optical disk substrate is fabricated by applying injection molding method.

14. The method for fabricating an optical disk as claimed in claim 13, wherein the information storing area forming step comprises:

forming at least one recording layer on top of the second upper surface of the second annular area;

forming a reflection layer on top of the at least one recording layer; and

forming a protection layer on top of the reflection layer.

15. The method for fabricating an optical disk as claimed in claim 13, wherein the information storing area forming step comprises:

forming a first dielectric layer on top of the second upper surface of the second annular area;

forming a recording layer on top of the first dielectric layer;

forming a second dielectric layer on top of the recording layer;

forming a heat dissipating layer on top of the second dielectric layer;

forming a reflection layer on top of the heat dissipating layer; and

forming a protection layer on top of the reflection layer.

16. The method for fabricating an optical disk as claimed in claim 12, wherein the step of fabricating the optical disk substrate includes:

fabricating a base plate having a third area and a fourth area, wherein the third area and the fourth area have the same thickness;

fabricating a compensation sheet, wherein the dimension of the compensation sheet is the same as that of the third area; and

assembling the compensation sheet and the base plate by joining the compensation sheet to the third area of the base plate.

17. The method for fabricating an optical disk as claimed in claim 16, wherein the information storing area forming step comprises:

forming at least one recording layer on top of the second upper surface of the second annular area;

forming a reflection layer on top of the at least one recording layer; and

forming a protection layer on top of the reflection layer.

18. The method for fabricating an optical disk as claimed in claim 16, wherein the information storing area forming step comprises:

forming a first dielectric layer on top of the second upper surface of the second annular area;

forming a recording layer on top of the first dielectric layer;

forming a second dielectric layer on top of the recording layer;

forming a heat dissipating layer on top of the second dielectric layer;

forming a reflection layer on top of the heat dissipating layer; and

forming a protection layer on top of the reflection layer.